

# Xuemiao Li

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/3394494/publications.pdf>

Version: 2024-02-01

10  
papers

113  
citations

1684188

5  
h-index

1720034

7  
g-index

10  
all docs

10  
docs citations

10  
times ranked

91  
citing authors

#	ARTICLE	IF	CITATIONS
1	Synthesis of Highly Ordered Si-Containing Fluorinated Block Copolymers. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2021, 34, 329-334.	0.3	0
2	Methacrylic Block Copolymers Containing Liquid Crystalline and Fluorinated Side Chains Capable of Fast Formation of 4 nm Domains. Macromolecules, 2020, 53, 8757-8764.	4.8	11
3	Poly(2-vinylpyridine)- <i>b</i> -poly(fluorinated methacrylate) Block Copolymers Forming 5 nm Domains Containing Metallocene. ACS Applied Polymer Materials, 2020, 2, 3601-3611.	4.4	11
4	Development of 90 NM & 5 NM High Resolution Advanced Lithographic Patterning Materials. , 2020, , .		0
5	Synthesis of a Fluoromethacrylate Hydroxystyrene Block Copolymer Capable of Rapidly Forming Sub-5 nm Domains at Low Temperatures. ACS Macro Letters, 2019, 8, 368-373.	4.8	43
6	Fast self-assembly of polystyrene- <i>b</i> -poly(fluoro methacrylate) into sub-5 nm microdomains for nanopatterning applications. Journal of Materials Chemistry C, 2019, 7, 2535-2540.	5.5	31
7	Synthesis of Liquid Crystalline Block Copolymers Self-assembled into Sub-5 nm Microdomains. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2019, 32, 413-416.	0.3	8
8	Ultra-Fast Block Copolymers for Sub-5 nm Lithographic Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 483-486.	0.3	5
9	Fast annealing DSA materials designed for sub-5 nm resolution. , 2018, , .		1
10	Synthesis and Directed Self-Assembly of Modified PS- <i>b</i> -PMMA for Sub-10 nm Nanolithography. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 83-86.	0.3	3